

# Application of Hi-F Coat for Recontamination Reduction at Shimane Unit 1

Hitachi-GE Nuclear Energy, Ltd.

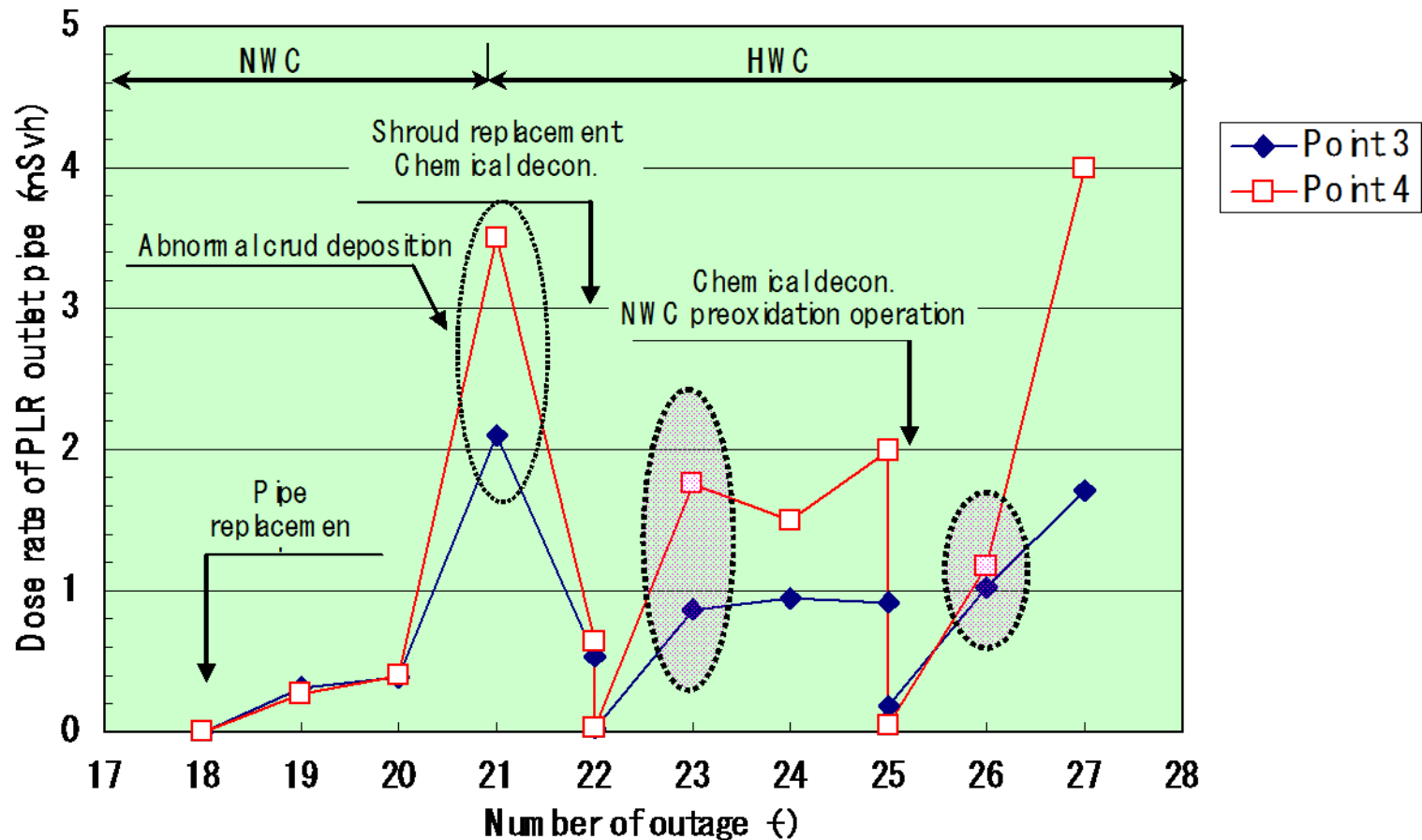
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- Dose rate reduction effects don't last long after operation.
- Recontamination reduction is needed to keep low dose rate.

		Film of Hi-F Coat	Oxide film in plants
Chemical form	Outer	$\text{Fe}_3\text{O}_4$	$\text{Fe}_3\text{O}_4$ 、 $\text{Fe}_2\text{O}_3$ 、 $\text{Ni (Co)Fe}_2\text{O}_4$
	Inner	—	$\text{CoCr}_2\text{O}_4$ 、 $\text{Cr}_2\text{O}_3$
Size of particle		$< 0.2 \mu\text{m}$	$1 \sim 10 \mu\text{m}$
Thickness of film		$< 0.5 \mu\text{m}$	$3 \sim 10 \mu\text{m}$
Temperature		$90^\circ\text{C}$	$280^\circ\text{C}$

## Principal of recontamination reduction

Formation of fine outer magnetite film before power operation

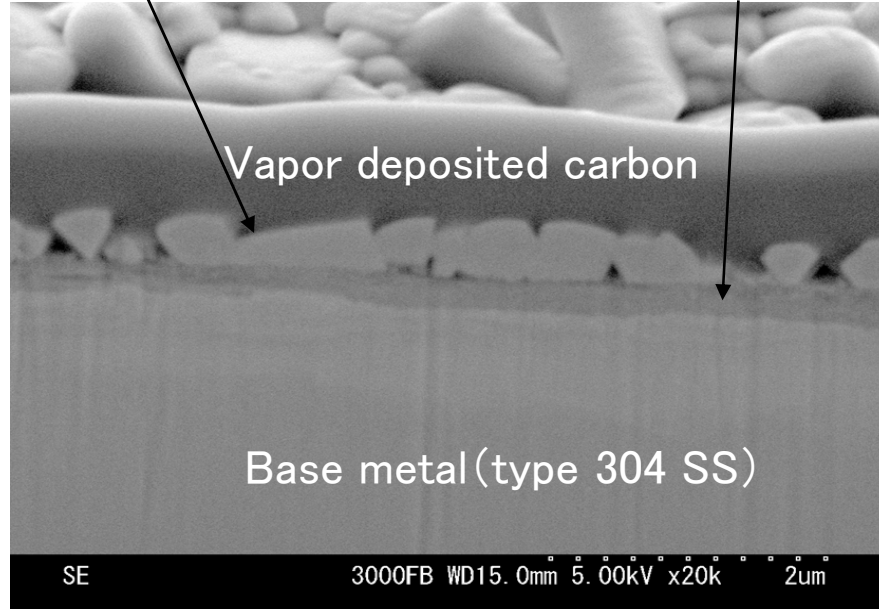
⇒ Reduction of inner oxide film formation to pick up Co

*Hi-F Coat : Hitachi Ferrite Coating*

Formation of fine magnetite film (thickness:  $\sim 0.3 \mu\text{m}$ )

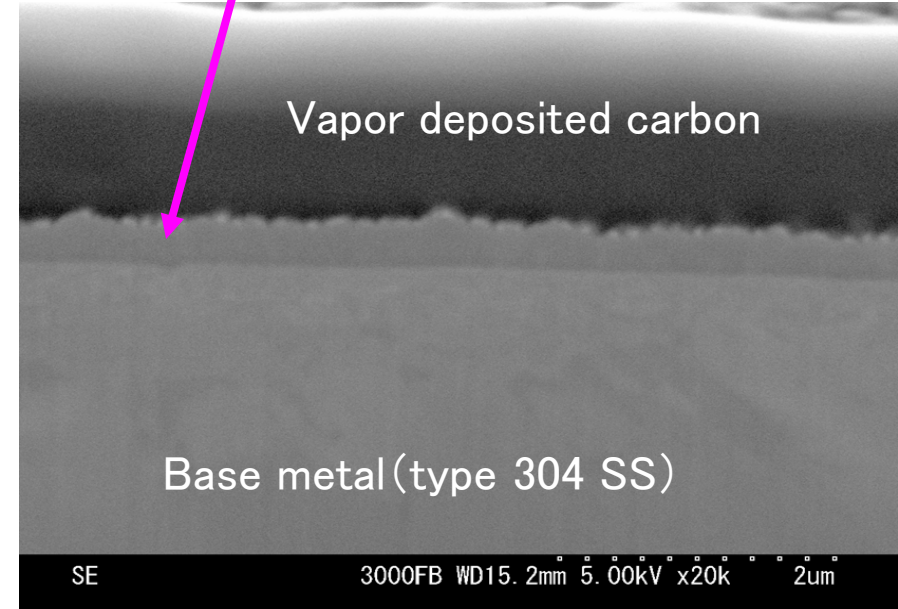
Outer (magnetite particle)

Inner (chromite)



Film formed under NWC 200h  
(DO: 300 ppb)

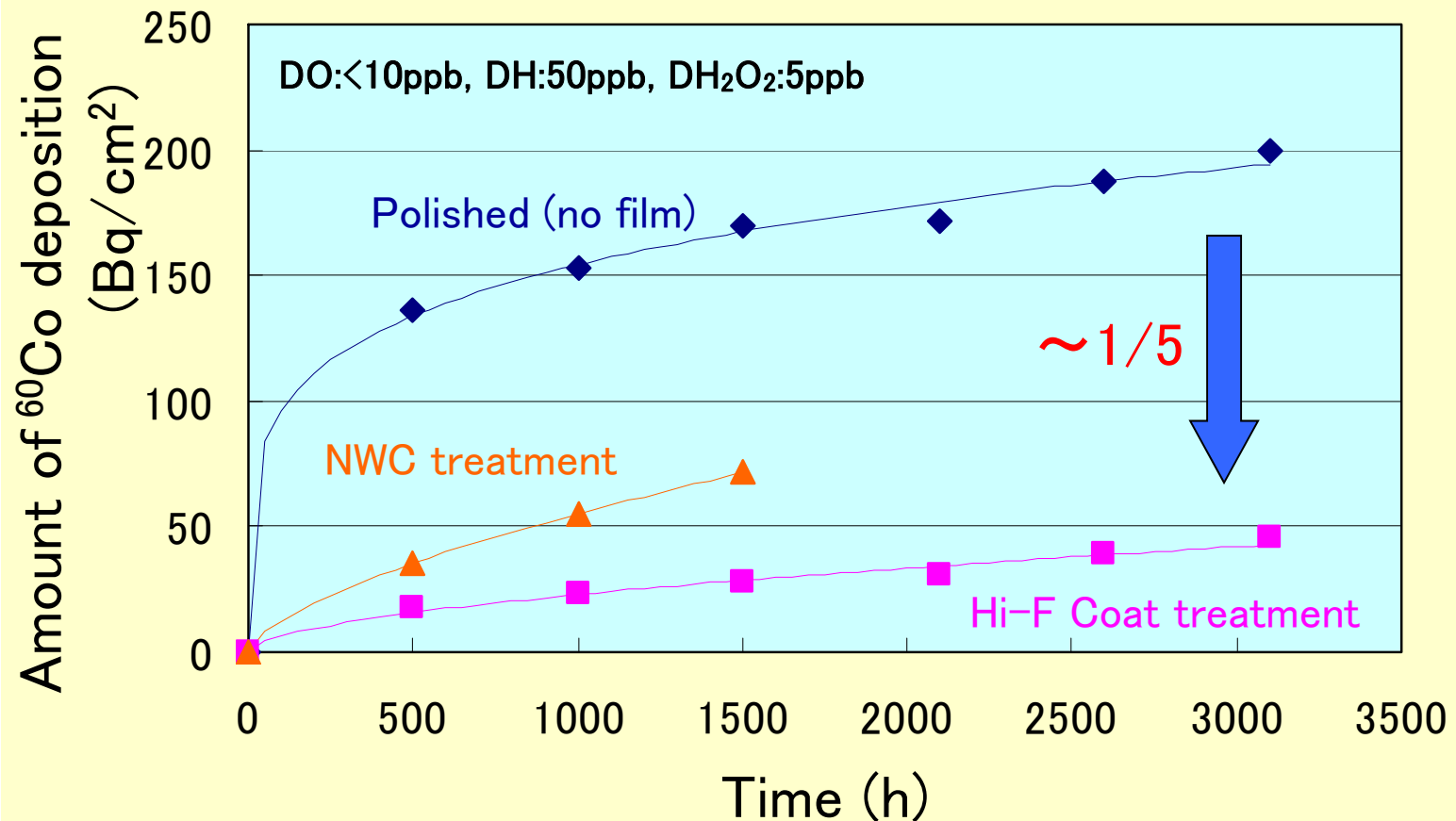
Coating layer (magnetite)



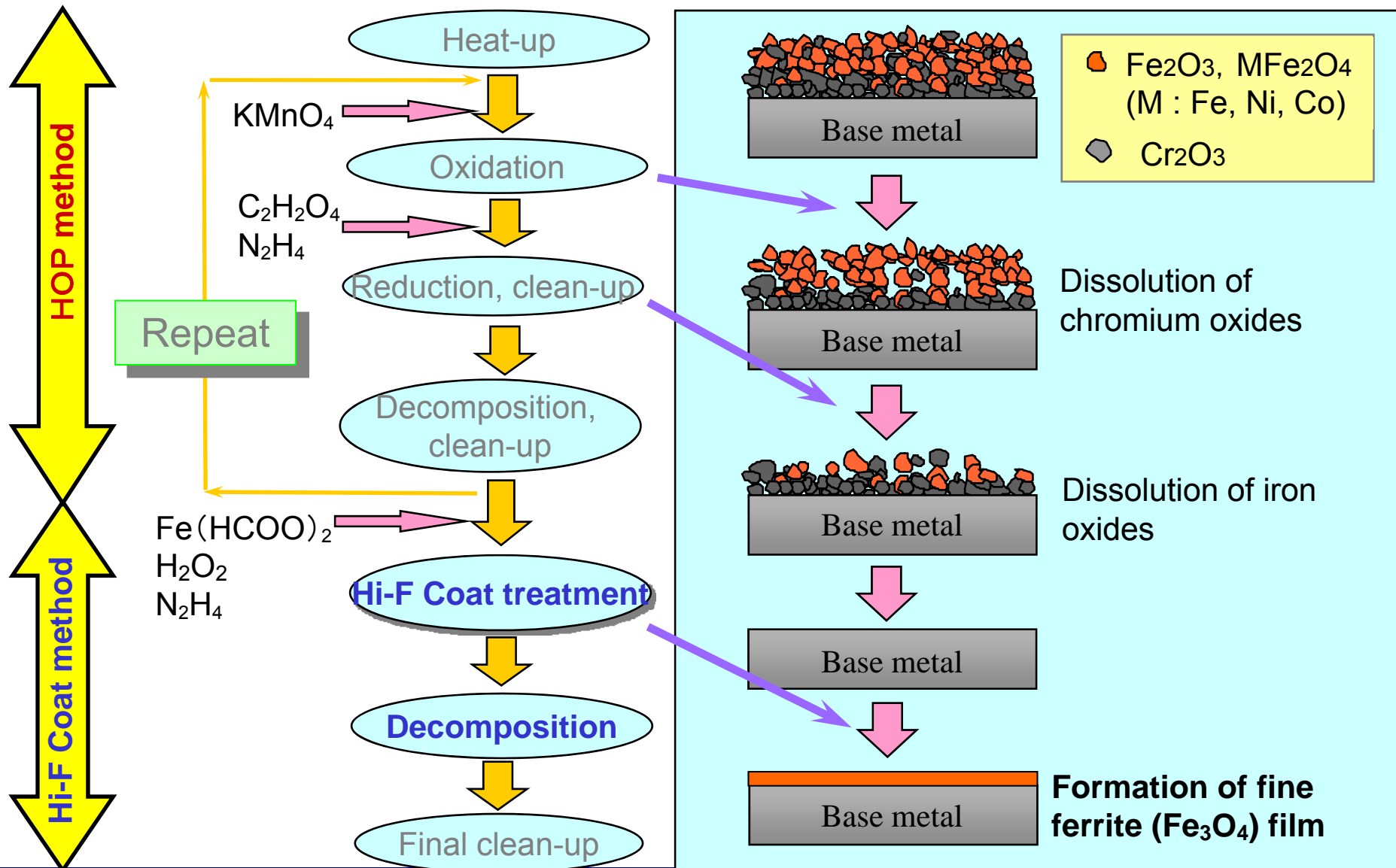
Film of Hi-F Caot

# Reduction effect of activity deposition (laboratory data)

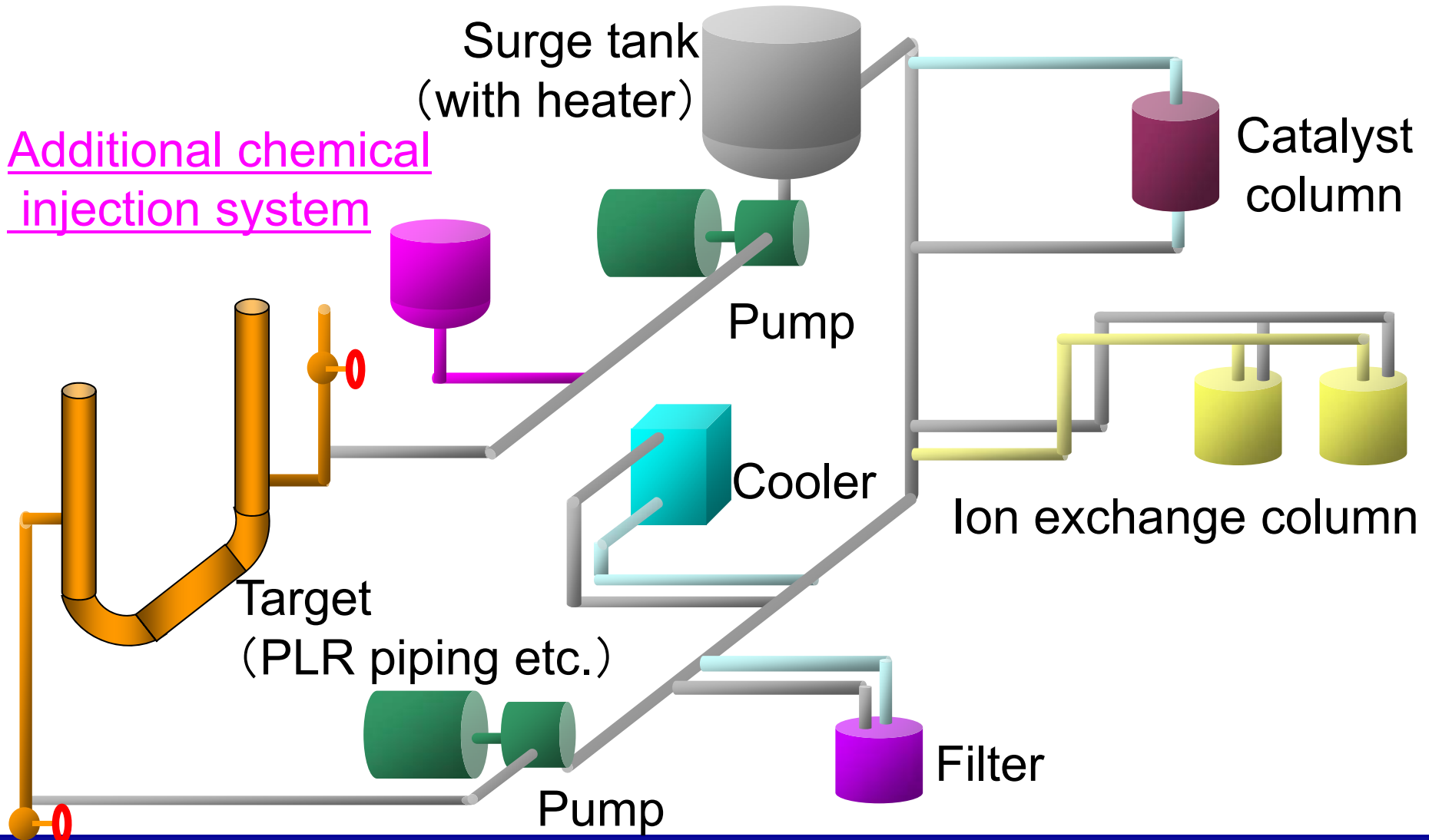
- Remarkable reduction of  $^{60}\text{Co}$  deposition under HWC
- Continuous effect after 6 times of heat and cool (Stable)



# Outline of treatment procedure



Only a little equipments are needed to decontamination equipments.



Only iron formate is added to HOP method chemicals.




	Chemical	Conc. (ppm)	Remarks
HOP decon. process	KMnO <sub>4</sub>	200~300	For oxidation
	(COOH) <sub>2</sub>	2000	For reduction
	N <sub>2</sub> H <sub>4</sub>	~600	For pH control
	H <sub>2</sub> O <sub>2</sub>	—	For decomposition of chemicals
Hi-F Coat treatment process	Fe(HCOO) <sub>2</sub>	Fe: ~ 250 Formic ion: ~ 500	Raw material for film formation Formic acid is used for LOMI* process.
	H <sub>2</sub> O <sub>2</sub>	—	For ion value control
	N <sub>2</sub> H <sub>4</sub>	200~500	For pH control

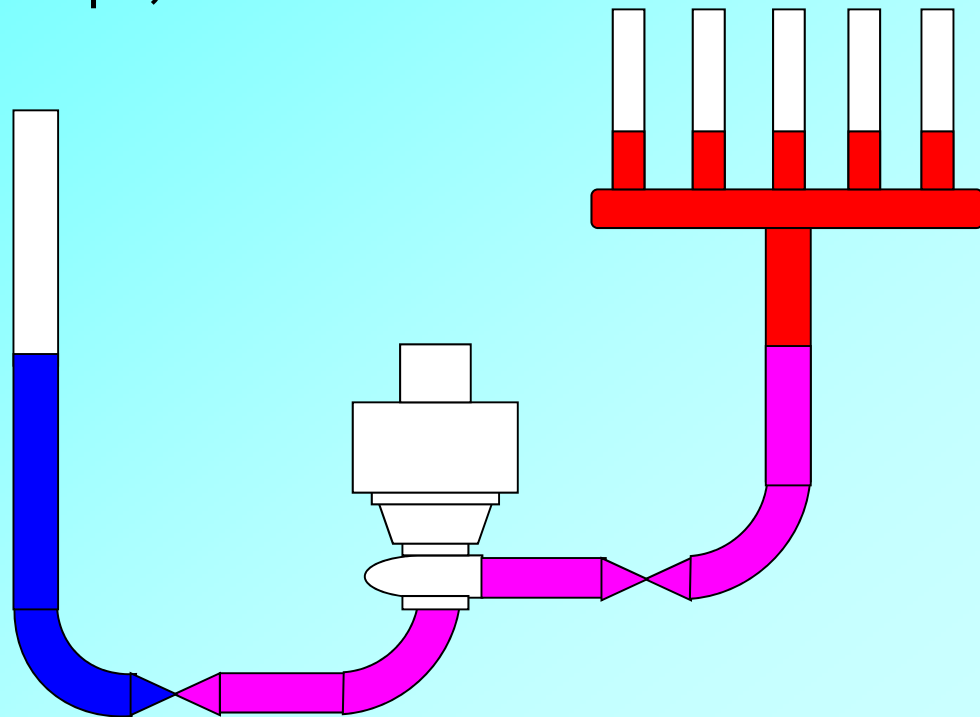
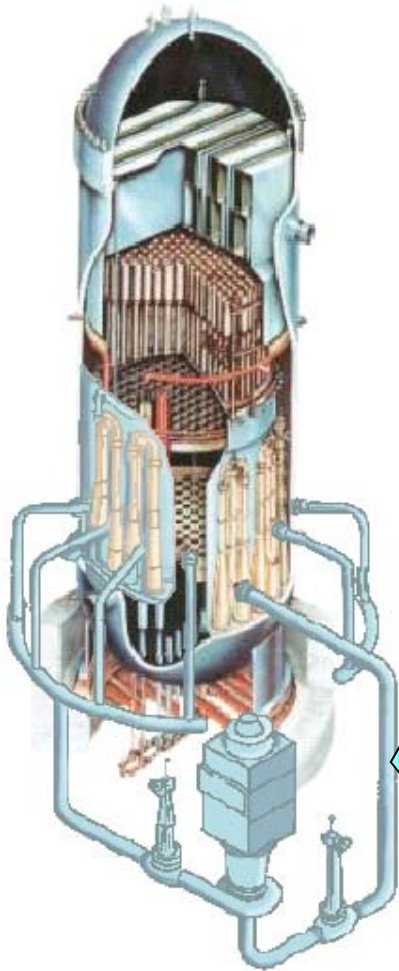
\*: LOMI is one of chemical decontamination method.



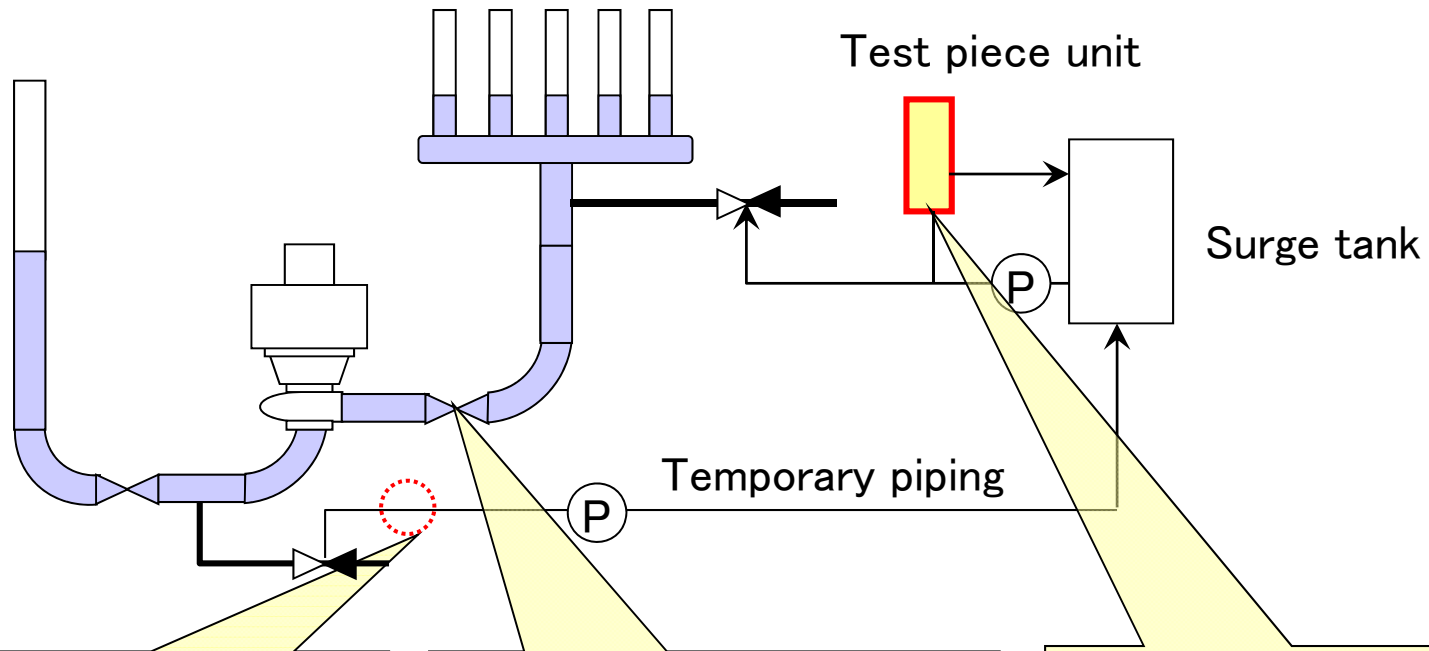
## PLR piping

- PLR pump inlet & outlet
- Ring header
- Riser piping (A & B loops)

	HOP	Hi-F Coat
	1 <sup>st</sup> time	1 <sup>st</sup> time
	1 <sup>st</sup> & 2 <sup>nd</sup> time	2 <sup>nd</sup> time
	2 <sup>nd</sup> time	2 <sup>nd</sup> time

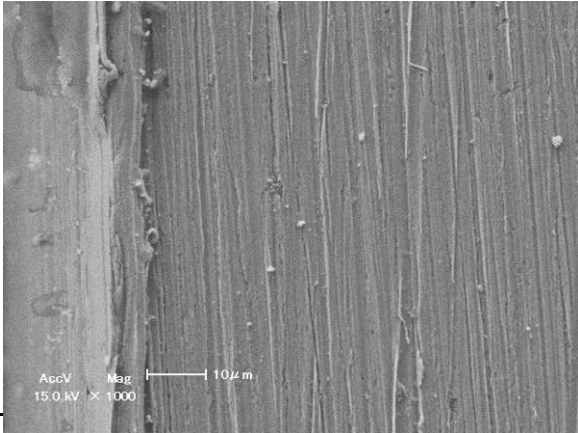
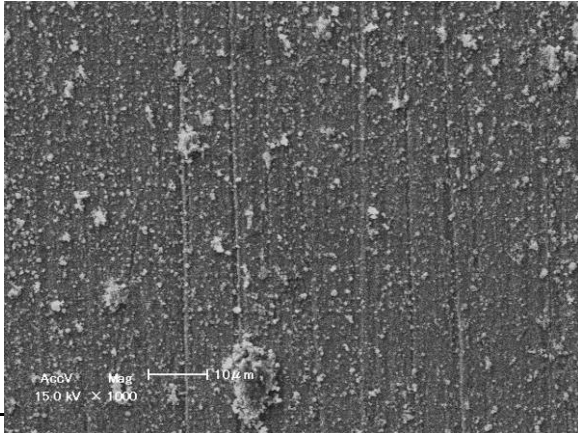
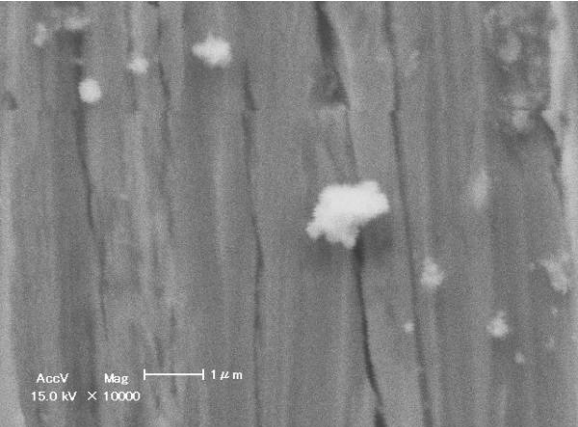
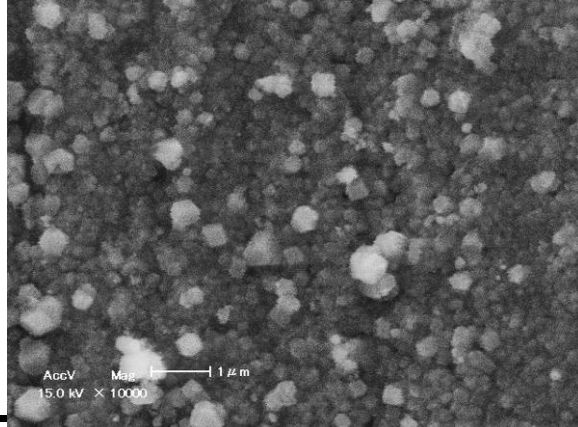


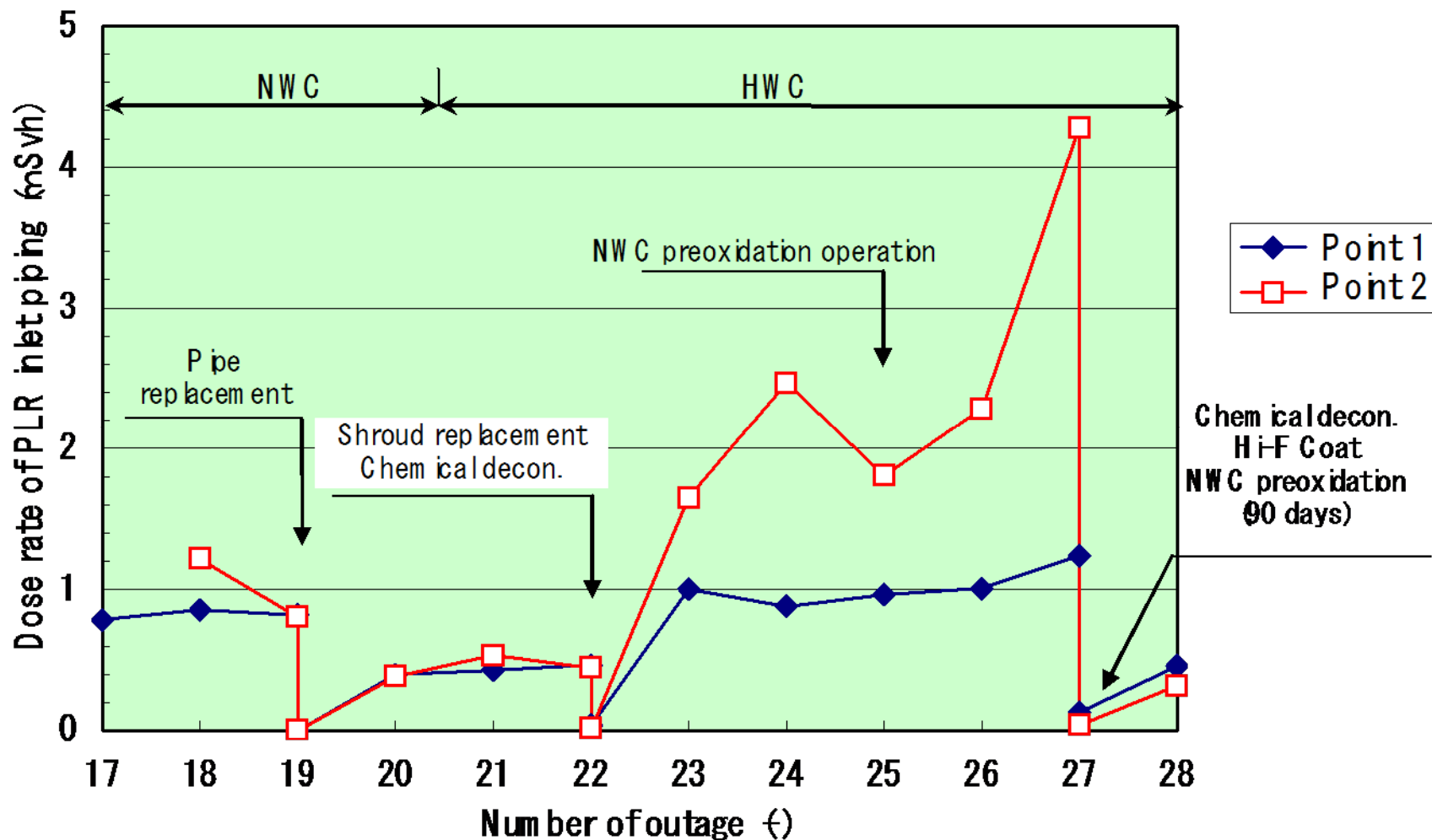
Parameter	Planned value	Measured value
Fe conc.	$250 \pm 50$ ppm	263 ~ 296 ppm
N <sub>2</sub> H <sub>4</sub> conc.	200 ~ 600 ppm	160 ~ 560 ppm

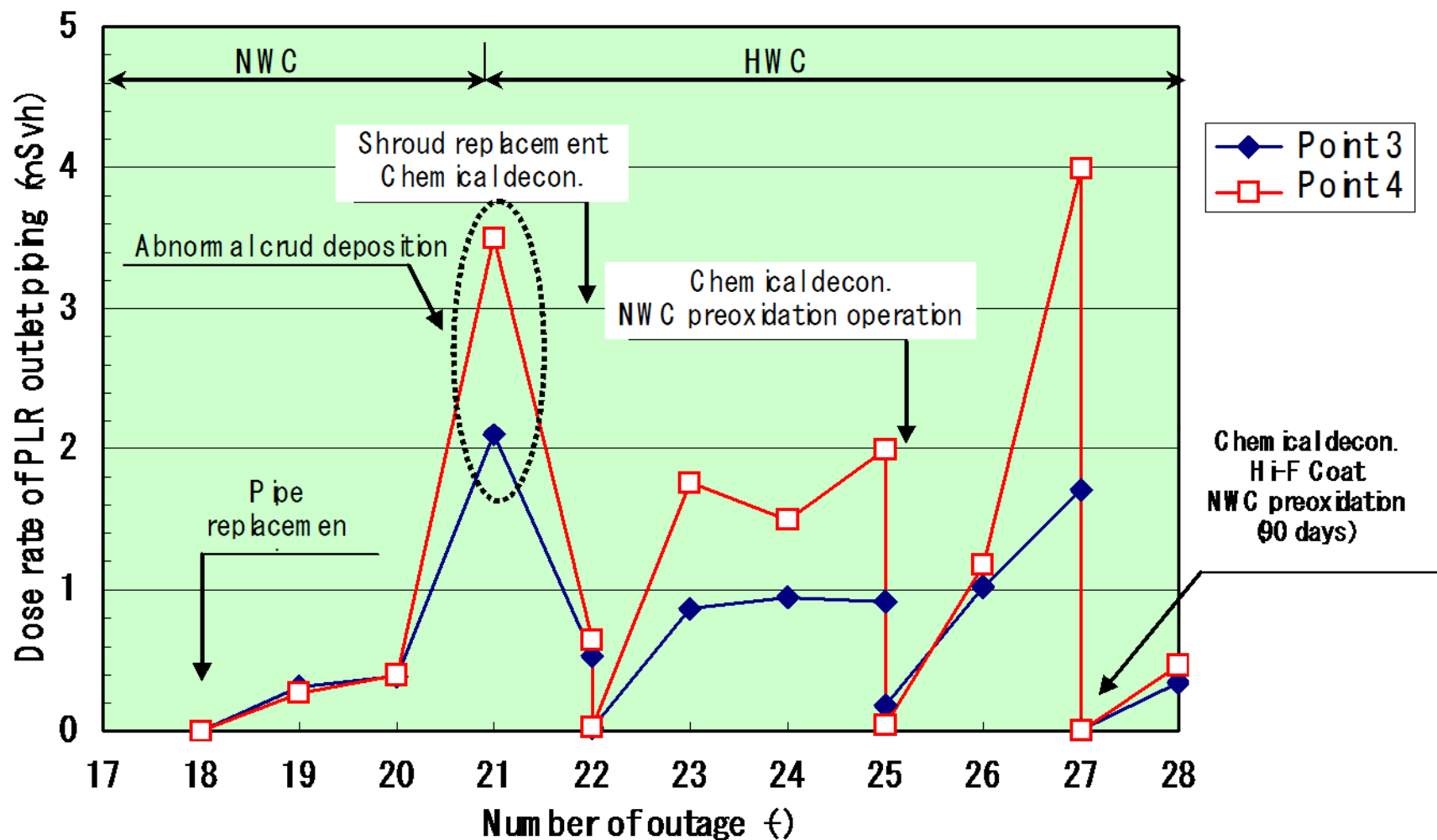


More than target value of  $0.1 \mu\text{m}$  ( $60 \mu\text{g}/\text{cm}^2$ ) was achieved.

Sample item	Application	Sample No.	Deposited amount ( $\mu\text{g}/\text{cm}^2$ )
Test piece	1 <sup>st</sup> time	1	230
		2	270
	2 <sup>nd</sup> time	3	302
		4	192
	3 <sup>rd</sup> time	5	125
		6	132
	4 <sup>th</sup> time	7	402
		8	498
Temporary piping	2 <sup>nd</sup> time	A	150
	4 <sup>th</sup> time	B	359

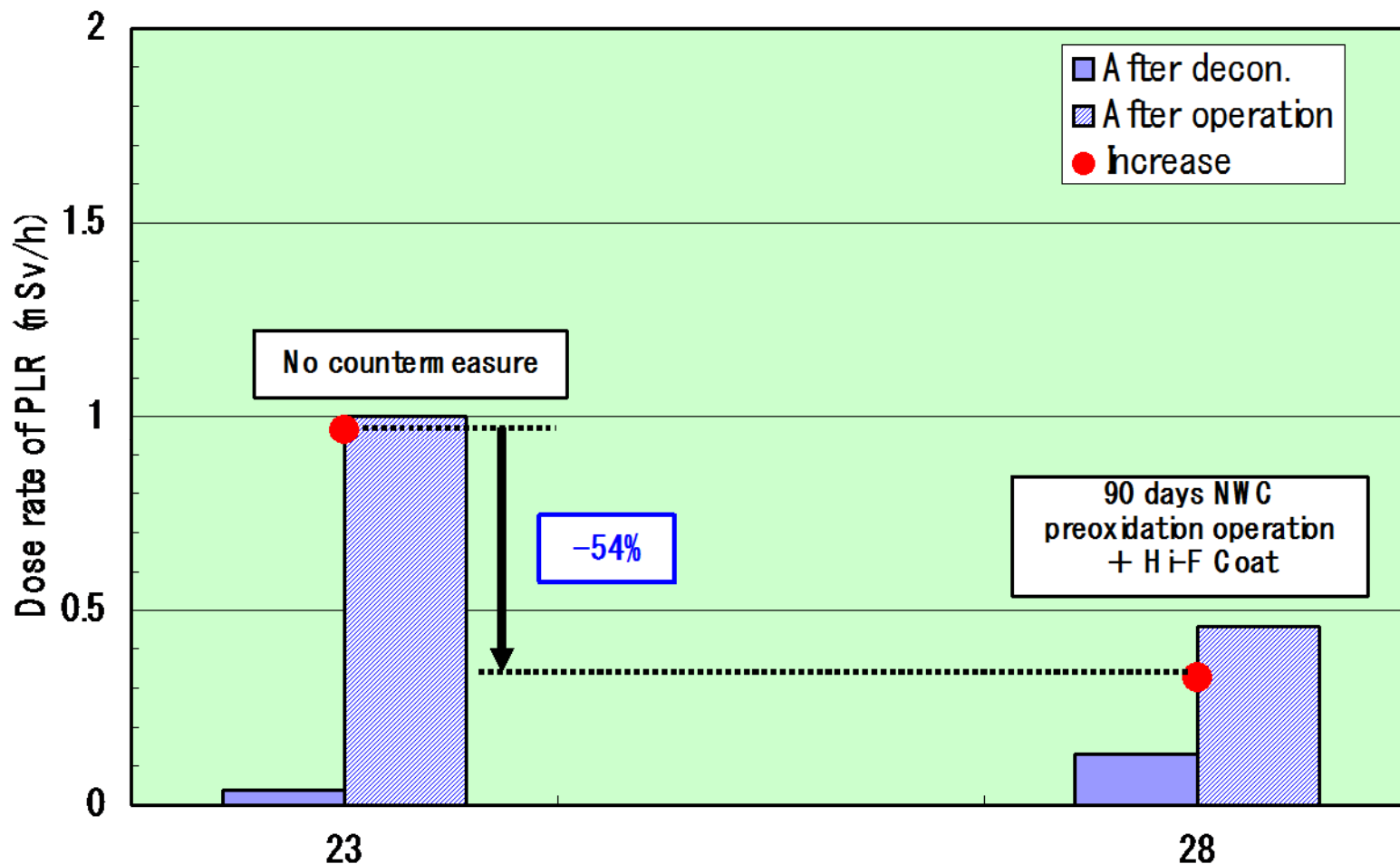
	Before Hi-F Coat (After decon.)	After Hi-F Coat
×1000		
×10000		





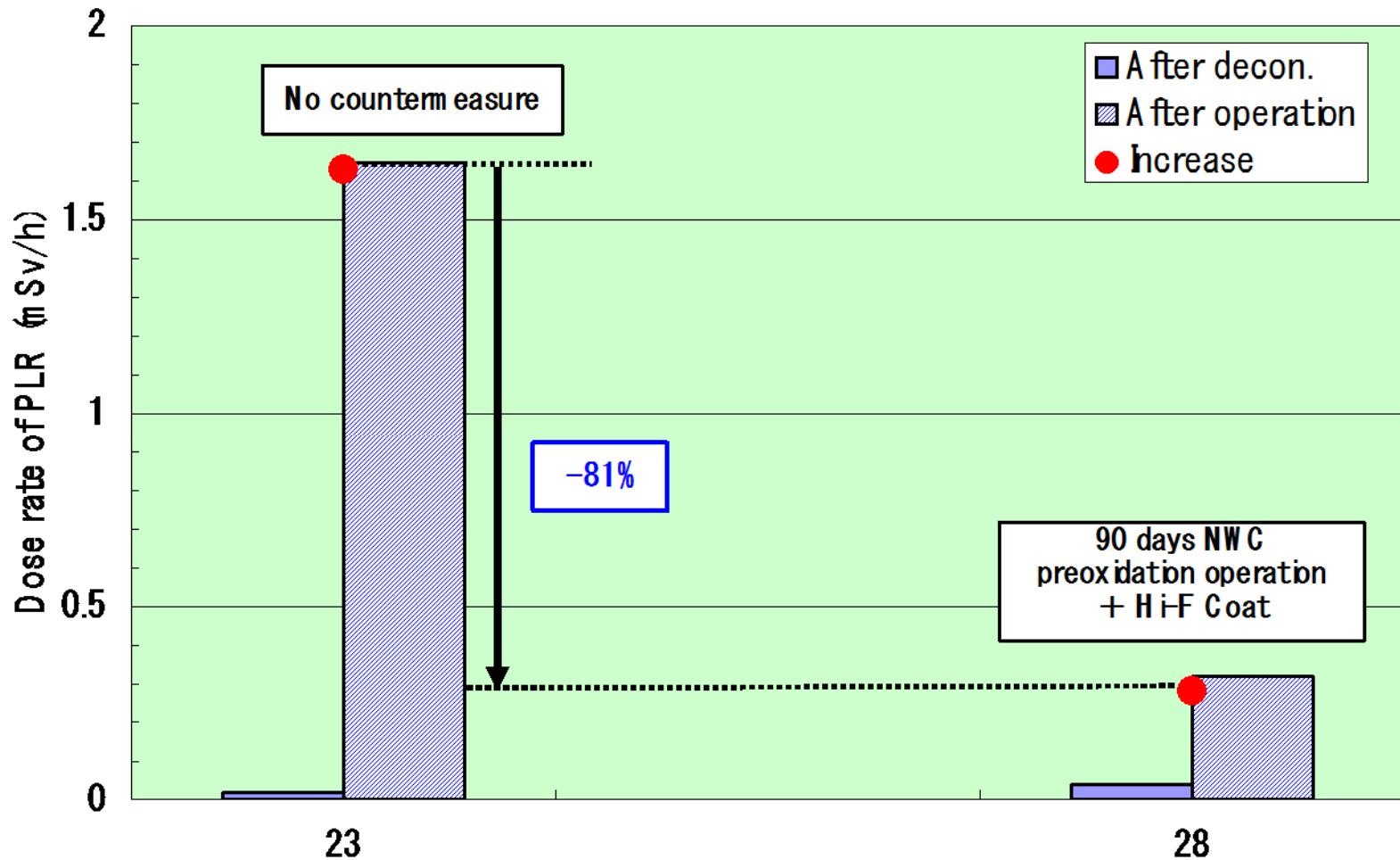


## Point 1: inlet piping

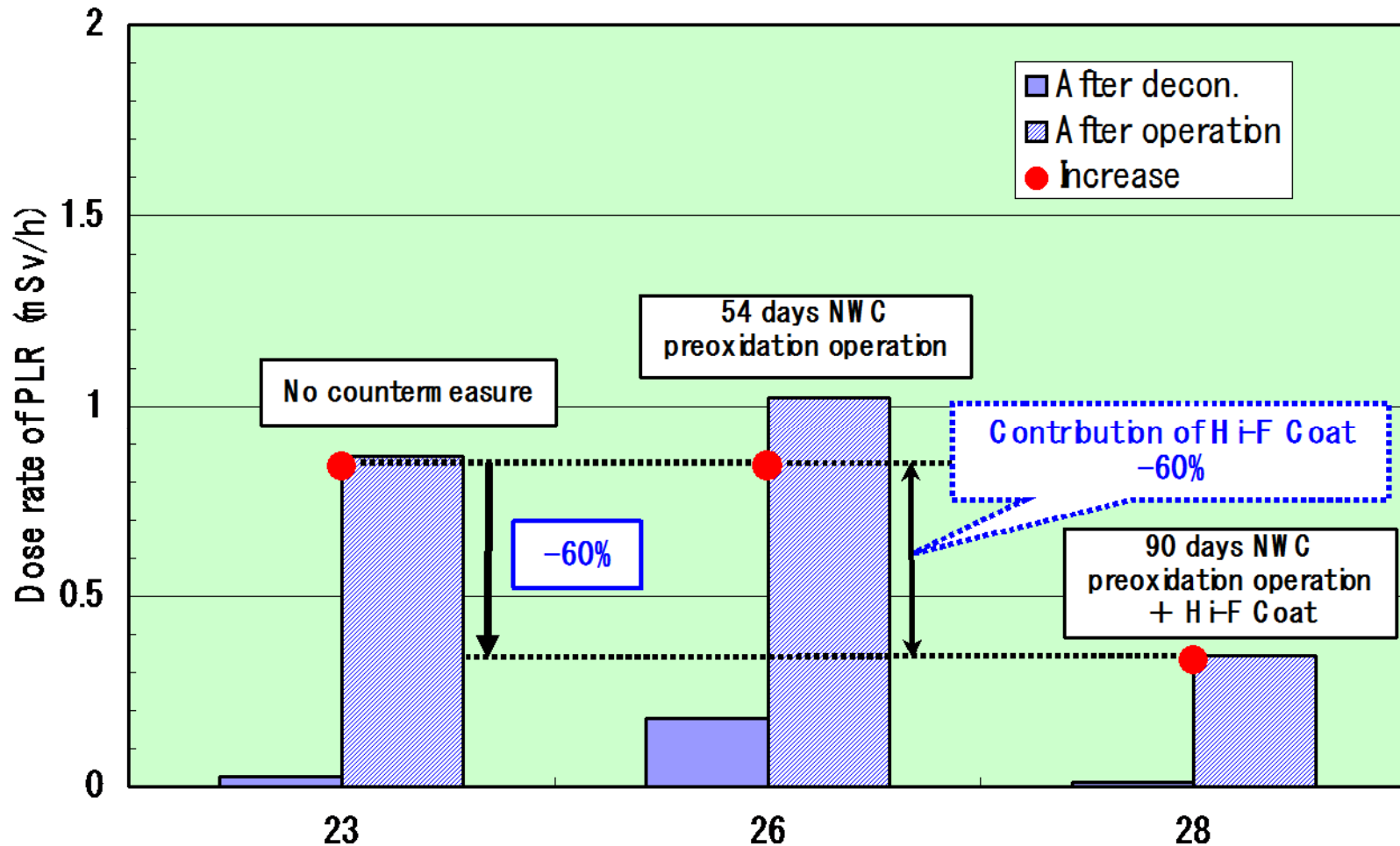




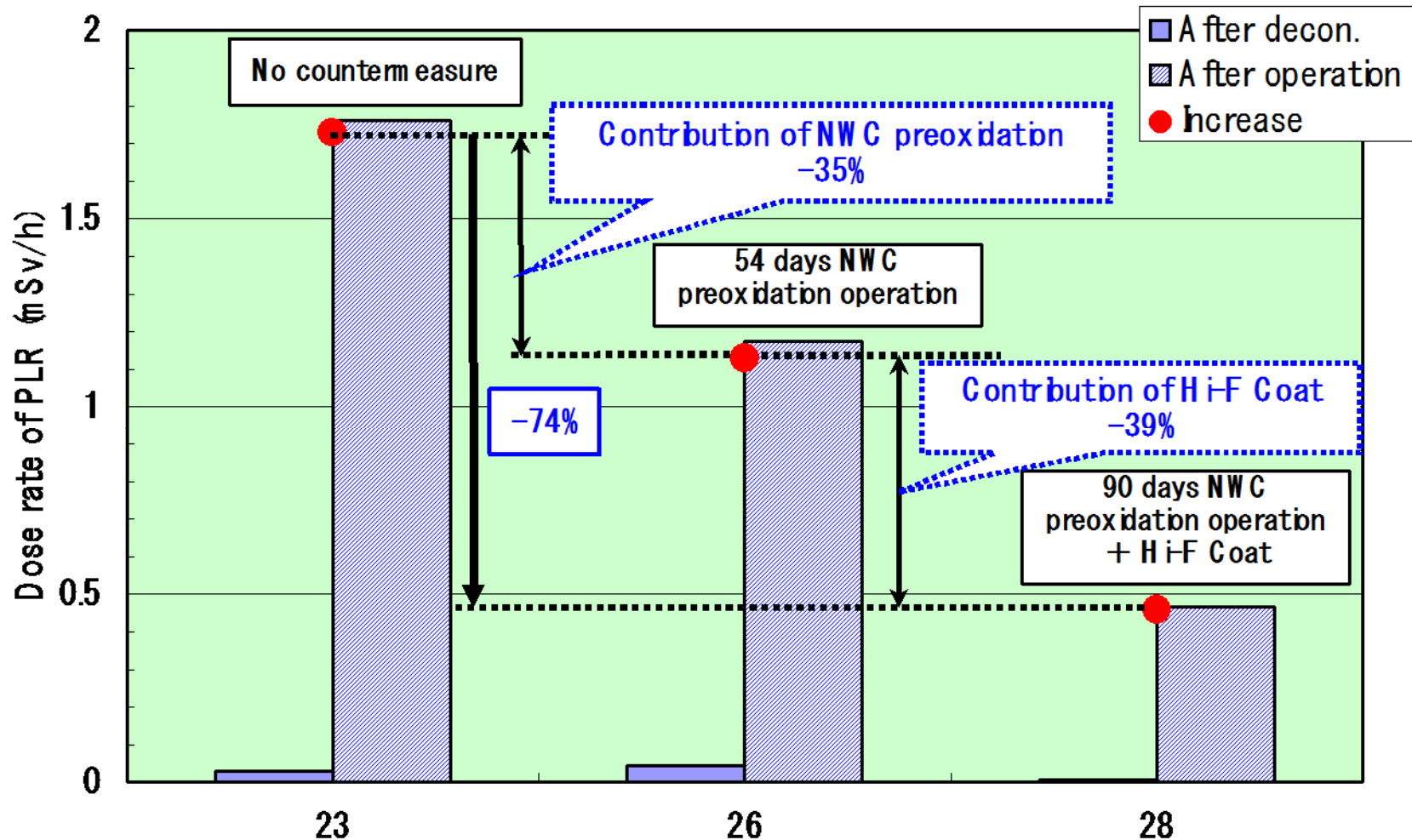
## Point 2: inlet piping



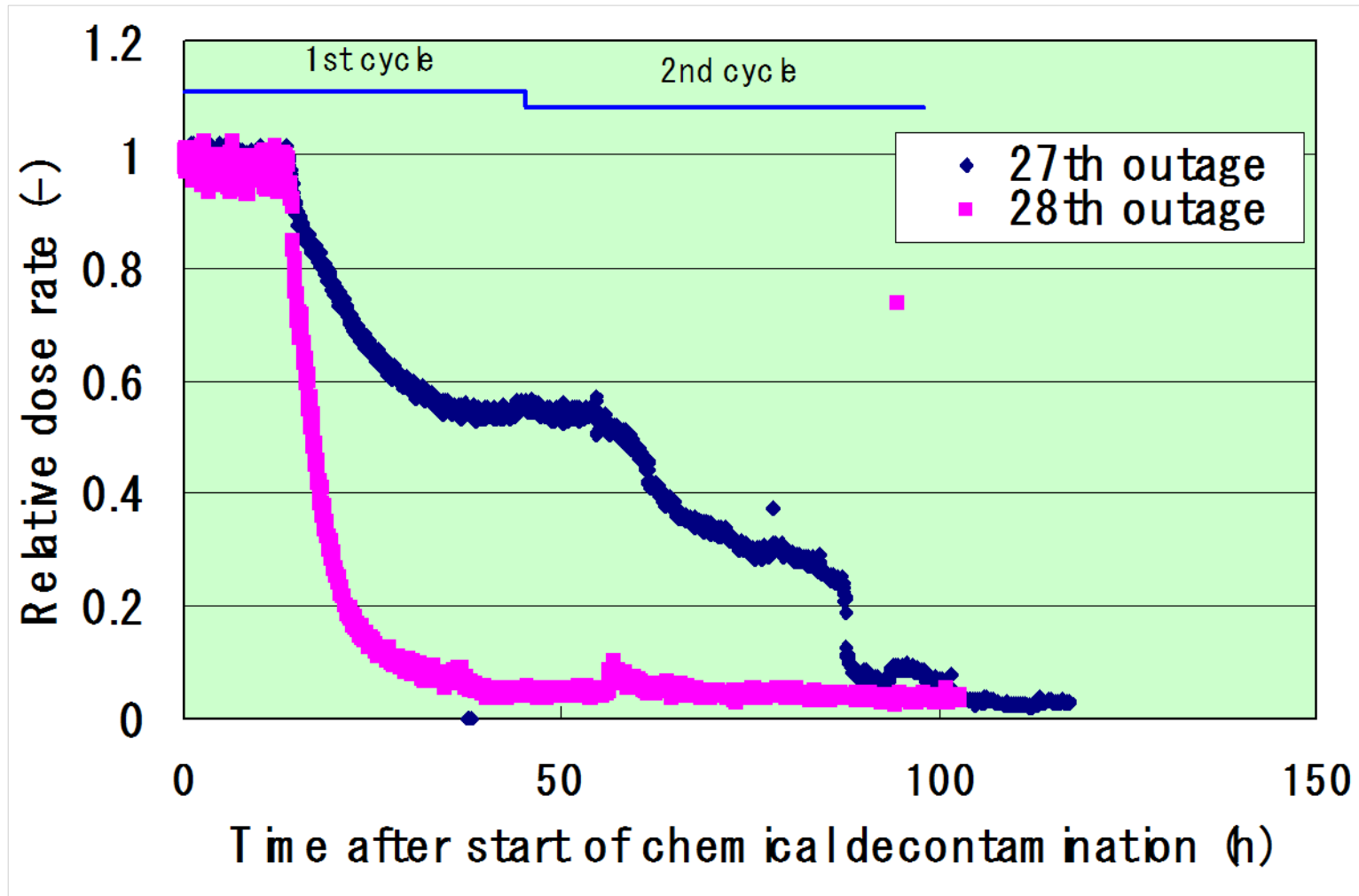
## Point 3: outlet piping



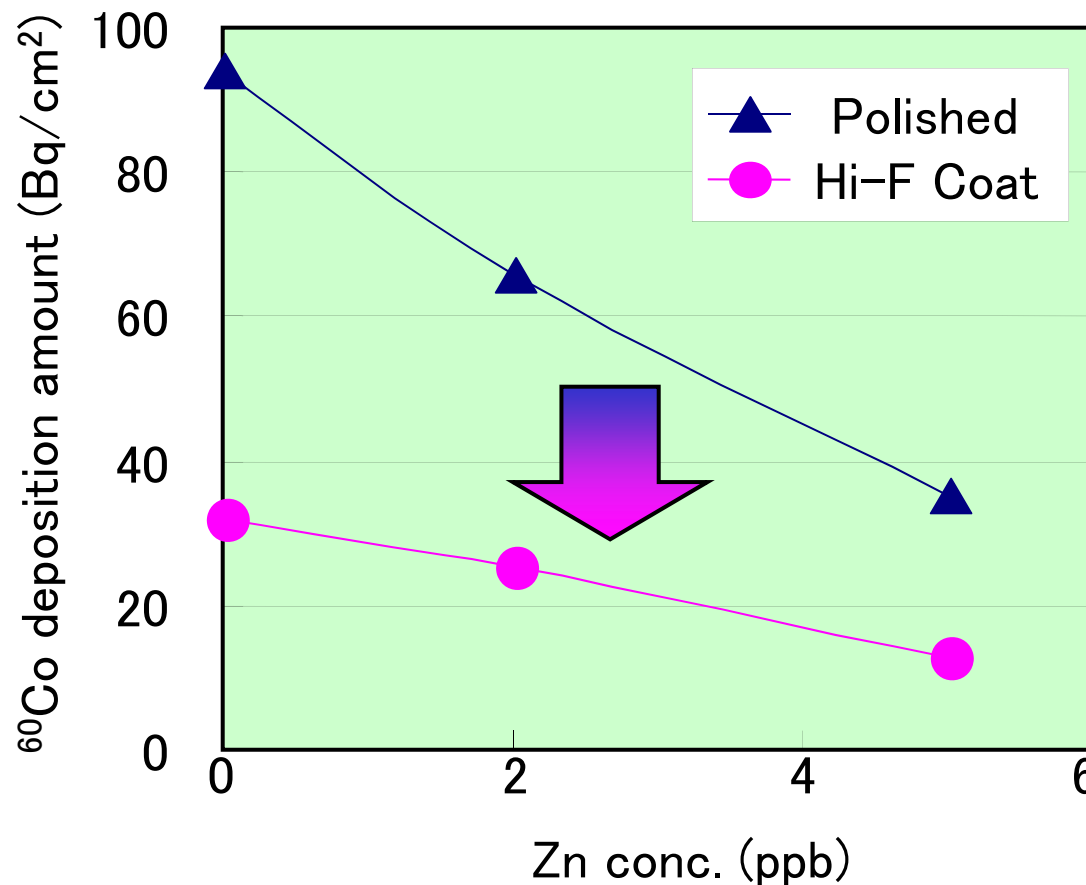
## Point 4: outlet piping



Hi-F Coat film was easy to be removed by chemical decontamination.



Farther Co deposition reduction can be expected with Zn injection.



Time : 500h  
Temp. : 280°C  
ECP : -0.5V

Hitachi laboratory data

1. Hi-F Coat was first applied to Shimane Unit 1 after chemical decontamination.
2. Hi-F Coat treatment was successfully applied to the decontaminated surface. Deposited amount of film was about  $270 \mu\text{g}/\text{cm}^2$  which was more than target value of  $60 \mu\text{g}/\text{cm}^2$ .
3. Recontamination was suppressed about 1/2 to 1/3 after one operation cycle.
4. Coated film was easy to be removed by chemical decontamination.
5. Farther dose rate reduction can be expected with Zn injection.